

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Attorney Docket No.: LAM1P124D1 In re application of: BAILEY III et al.

Examiner: ALEJANDRO MULERO, L. Application No.: 09/943,806

Group: 1763 Filed: August 30, 2001

Title: TEMPERATURE CONTROL SYSTEM FOR PLASMA PROCESSING APPARATUS

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to Box Non-Fee Amendment, Commissioner for Patents, Washington, D.C. 20231 on November 27, 2002.

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AMENDMENT C TRANSMITTAL

Box Non-Fee Amendment Commissioner for Patents Washington, D.C. 20231

Transmitted herewith is an Amendment in the above-identified application. The fee has been Sir:

llculated as sho	Claims After		Highest Previously Paid For	Present Extra	Small Entity Rate Fee	Large Entity Rate Fee
	Amendment	MINUS	20	0	x 9 =	x 18 = \$-0-
Total Claims	14	MINUS	20	-	12	x 84 = \$-0-
Independent	03	MINUS	03	0	x 42 =	
Claims		at and E	Not Previously Paid		\$140.00	\$280.00
Claims Multiple Dependent Claim Present and Fee Not Previously Paid Total				Total	\$	\$0.00

	Applicant(s) hereby petition for a month extension(s) of time to respond to the
	forementioned Office Action.
\sum	Applicant(s) believe that no (additional) Extension of the determined that such an extension is required, Applicant(s) hereby petition that such an extension of Time
	be granted and authorize the Commissioner to charge the required by the granted and authorize the Commissioner to charge the required by under 37 CFR 1.136 to Deposit Account No. 50-0388 (Order No. LAM1P124D1). Under 37 CFR 1.136 to Deposit Account No. 50-0388 (Order No. LAM1P124D1). Enclosed is our Check No in the amount of \$ to cover the additional control of the property of the
	Enclosed is our Check No in the amount of the claim fee and/or extension of time fees.
	Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the required fees, or any additional fees required to the Please charge the Please charge the Please charge the required fees, or any additional fees required to the Please charge the Please charg

Respectfully submitted, BEYER WEAVER & THOMAS, LLP

Francis T. Kalinski II Reg. No. 44,177

P.O. Box 778 Berkeley, CA 94704-0778



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Signed:

AMENDMENT C

Box Non-Fee Amendment Commissioner for Patents Washington, DC 20231

Sir:

This Amendment is in response to the Office Action (identified as paper no. 10) mailed October 10, 2002. Applicants representative kindly thanks the Examiner for her helpful guidance during the telephonic interview of November 26, 2002. Applicant's representative respectfully requests entry of this amendment. Please amend the above-entitled application as set forth below.

In The Claims:

Please **CANCEL**, without prejudice, claims 24, 25, and 34 as follows.

Please **AMEND** the claims as follows:

(Twice amended) 23. A method for providing temperature control to a plasma processing chamber of a plasma processing apparatus, said method comprising:

directly or indirectly measuring temperature internal to the plasma processing chamber: